# LabAdviser update: 19/1 2022

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| Updated Subject  | Contributor | Link to the updated pages |
| Sputter-System Metal-Oxide (PC1)* Sputtering of NiV in Sputter-System Metal-Oxide (PC1):
* TiO2 deposition using Sputter-System Metal-Oxide(PC1):
* Deposition of silicon nitride using Sputter-System Metal-Oxide(PC1):
* Si sputter in Sputter-System Metal-Oxide(PC1):
 | **Evgeniy Shkondin @Nanolab** | [Sputtering of NiV in Sputter-System Metal-Oxide (PC1)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_NiV/Sputtering_of_NiV_in_Sputter-System_Metal-Oxide_%28PC1%29)[TiO2 deposition using Sputter-System Metal-Oxide(PC1](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/TiO2_deposition_using_Sputter-System_Metal-Oxide%28PC1%29)[Deposition of silicon nitride using Sputter-System Metal-Oxide(PC1)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Silicon_Nitride/Deposition_of_silicon_nitride_using_Sputter-System_Metal-Oxide%28PC1%29)[Si sputter in Sputter-System Metal-Oxide(PC1)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Silicon/Si_sputter_in_Sputter-System_Metal-Oxide%28PC1%29) |
| **Sputter-system Lesker (’old Lesker’)*** TiO2 deposition using Sputter System (Lesker)
* Si sputter in Sputter System (Lesker) – page has been updated with RF sputtering of Si
* Pt sputter in Sputter System (Lesker)
* ZnO sputter in Sputter System (Lesker)
* Al sputter in Sputter System (Lesker):
* Cr sputter in Sputter System (Lesker):
* Ti sputter in sputter system (Lesker):
 | **Evgeniy Shkondin @Nanolab** | [TiO2 deposition in Sputter System (Lesker)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/TiO2_deposition_in_Sputter_System_%28Lesker%29)[Si\_sputter\_in\_Sputter-System\_Lesker](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Silicon/Si_sputter_in_Sputter-System_Lesker)[Deposition of Pt in Sputter System (Lesker)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Platinum/Deposition_of_Pt_in_Sputter_System_%28Lesker%29)[ZnO deposition in Sputter System (Lesker)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_ZnO/ZnO_deposition_in_Sputter_System_%28Lesker%29)[Al sputtering in Sputter System (Lesker)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Aluminium/Al_sputtering_in_Sputter_System_%28Lesker%29)[Sputtering of Cr in Sputter System (Lesker)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Chromium/Sputtering_of_Cr_in_Sputter_System_%28Lesker%29)[Ti deposition in Sputter System (Lesker)](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Titanium/Ti_deposition_in_Sputter_System_%28Lesker%29) |
| **Ellipsometer**Link to our training video, under ‘before training’ | **Berit Herstrøm and Thomas Pedersen @Nanolab** | [Optical\_characterization#More\_details](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Optical_characterization#More_details) |
| **BHF etch rates**Some updated etch rates (in October) | **Karen Birkelund @Nanolab** | [Etch/Wet\_Silicon\_Oxide\_Etch\_(BHF)/BHF\_etch\_rates](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Wet_Silicon_Oxide_Etch_%28BHF%29/BHF_etch_rates) |
| **XPS**Complete instructions + files to* Download/installation/ of Avantage
* Download/installation/ of CasaXPS
* Export af Avantage data to CasaXPS
 | **Jonas Michael-Lindhard @Nanolab** | [/Characterization/XPS#Analyzing\_XPS\_spectra](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XPS#Analyzing_XPS_spectra) |
| **Oxidation furnaces A1 and A3**Measurements of breakdown voltage for dry oxide and wet oxide on furnaces A1 and A3 | **Pernille V. Larsen and Patama Pholprasit @Nanolab** | [/Thermal\_Process/Oxidation/Breakdown\_voltage\_measurements](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thermal_Process/Oxidation/Breakdown_voltage_measurements) |

# Equipment Manuals updated in LabManager (since 1nst of November):

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.
Manual for Nikon ECLIPSE L200 optical microscope, ver 5.4

Manual for Sputter Coater 04, ver 2

Manual for Sputter Coater 03, ver 3

Manual for ALD 2 (PEALD), ver 2.3

Manual for RTP Jipelec, ver 7.2

Manual for Spin Coater: Gamma UV, ver 2

Manual for III-V Plassys RIE, ver 3.3

DUV STEPPER job file creation manual, ver 3

Manual for Spin Coater: Gamma e-beam & UV, ver 2.2

Manual for Furnace: Oxidation (8") (E1), ver 1

Manual for Lifetime scanner MDPmap, ver 4

APV Developer: TMAH Manual, ver 3.2

APV and manual for fume hoods in the cleanroom, ver 6

Manual for Developer: SU8, ver 7.1

Manual for Oven 250C, ver 3

Manual for SÜSS Spinner-Stepper., ver 4

Manual for Developer TMAH Stepper., ver 3.2

Manual for Hotplate: 90-110C, ver 2.3

Manual for Developer TMAH UV-lithography, ver 3.2

Manual for Wordentec, ver 12

Manual for LPCVD Nitride Furnace (4"), ver 7.2

Manual for LPCVD polysilicon furnace (4"), ver 6.3

Manual for Dektak 3ST, ver 9

Manual for Leitz Medilux optical microscope, ver 2.3

Manual for Leica S8 APO optical microscope, ver 2.3

Manual for Zeiss Jenatech (particle measturements) optical microscope,

Manual for Nikon ME 600 optical microscope, ver 2.3

Manual for Microscope: Zeiss Axiotron 2, ver 2.1

Manual for Microscope: Nikon Eclipse L200N 3 and 4, ver 1.1

Dicing Saw: DAD 3241, ver 1